

Supplementary Information

Giant optical anisotropy in transition metal dichalcogenides for the next-generation photonics

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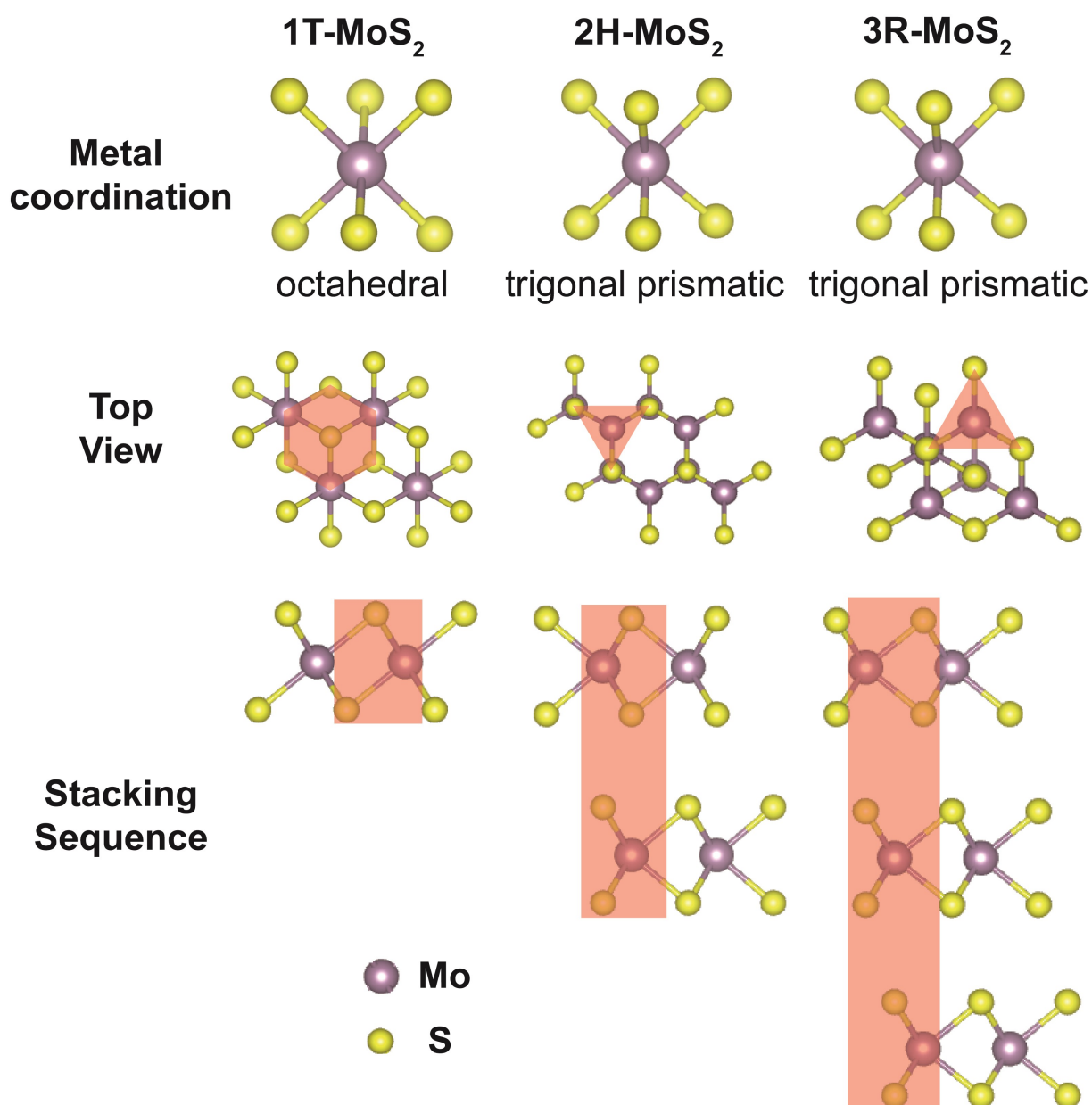
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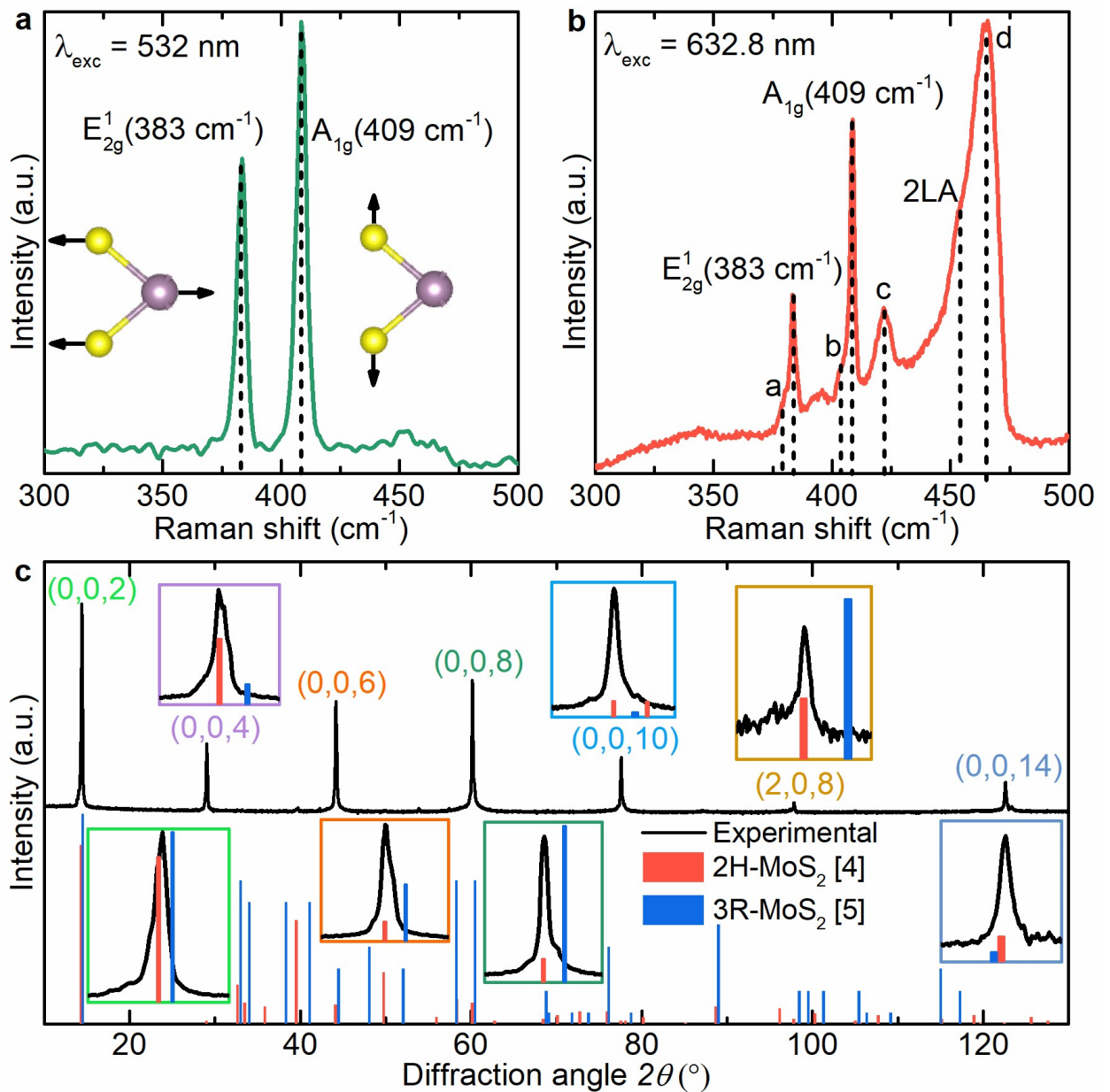
27 **Supplementary Note 1: Crystal characterization of 2H-MoS₂**

28 Bulk MoS₂ is found to exist in three polymorphic states (different stacking sequences of
29 monolayers with the same structure) shown in Supplementary Figure 1: 1T (tetragonal), 2H
30 (hexagonal), and 3R (rhombohedral) with the integer referring to the number of layers in the unit
31 cell. To verify our sample's crystal structure, we performed Raman spectroscopy at 532 and 632.8
32 nm with x-ray diffraction characterization shown in Supplementary Figure 2. Raman spectra
33 allows easily to distinguish 1T-phase since it has fundamental modes $E_{1g} = 292 \text{ cm}^{-1}$ and $A_{1g} =$
34 402 cm^{-1} ,¹ whereas their positions $E_{1g} = 383 \text{ cm}^{-1}$ and $A_{1g} = 408 \text{ cm}^{-1}$ for 2H- and 3R-states are the
35 same owing to their similar in-plane atoms arrangement.² Luckily, Lee and co-workers thoroughly
36 analyzed Raman spectra for these phases.³ They proved that the presence of 3R-phase in 2H-
37 configuration is accompanied by the significant magnification of intensities for *a*- and *b*-peaks at
38 $\lambda_{\text{exc}} = 632.8 \text{ nm}$ (see Supplementary Figure 2a-b), which is absent in our case. Thus, it validates
39 2H-MoS₂ purity of the samples. As an additional verification, we performed x-ray diffraction
40 (XRD) analysis and unambiguously checked the crystal structure because 2H- and 3R-
41 configurations result in different diffraction^{4,5} patterns shown in Supplementary Figure 2b. Apart
42 from crystal structure, XRD also provides information about crystallographic parameters, which
43 in our case $a = b = 0.310 \pm 0.005 \text{ nm}$ and $c = 1.229 \pm 0.001 \text{ nm}$.



44

45 **Supplementary Figure 1.** Crystal structure of the MoS₂ polytypes: 1T-, 2H-, and 3R-
 46 configurations. The red boxes denote the unit cell.



47

48 **Supplementary Figure 2. Crystal characterization.** Raman spectra in **a** non-resonant (excitation
 49 wavelength does not induce exciton) and **b** resonant (excitation wavelength induces exciton)
 50 conditions. The positions of two first-order Raman modes, namely E_{2g}^1 and A_{1g} , correspond to
 51 2H-MoS₂. **c** X-ray measurements (using Cu-K α radiation ($\lambda = 0.1542 \text{ nm}$)) allows to distinguish
 52 2H- from 3R-configuration^{4,5} of MoS₂. The insets in (c) shows the magnified diffraction orders.

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54 **Supplementary Note 2: Ellipsometry measurements and analysis**

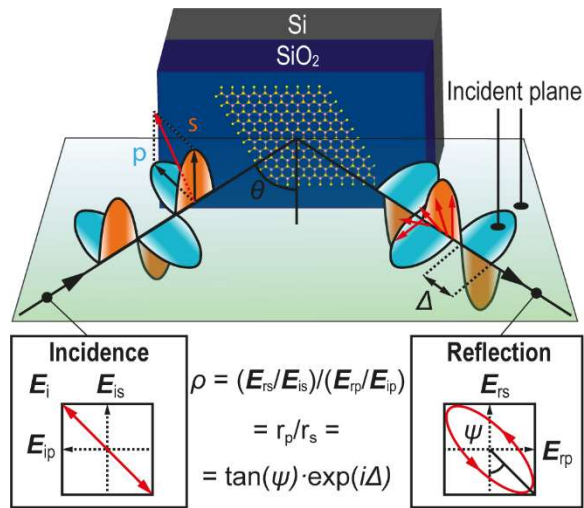
55 We characterize the far-field optical response of MoS₂ through imaging spectroscopic
56 ellipsometry,⁶ which configuration is schematically shown in Supplementary Figure 3. The major
57 advantage of imaging over conventional ellipsometry is multiple samples measurements within
58 the same field of view, as illustrated in Figure 1b. As a result, we have multiple spectra in
59 Supplementary Figure 4 for the same system MoS₂/SiO₂/Si, but with different thicknesses (104
60 and 126 nm). Therefore, we model them simultaneously with equal dielectric permittivities. Such
61 an approach gives the most accurate results since it increases data reliability and reduces the
62 correlation between fitting parameters. At the same time, to adequately describe optical constants,
63 it is imperative to obtain a good initial guess for refractive indices for software to find the right
64 answer and a physical model. To overcome the first problem we proceeded in the following way:
65 in the transparent range (800 – 1700 nm) both in-plane and out-of-plane components were
66 described by a Cauchy model $A + B/\lambda^2$, then we performed Kramers-Kronig consistent B-spline
67 expansion⁷ for the whole spectral interval (360 – 1700 nm) for in-plane dielectric permittivity.
68 Later we leveraged the Tauc-Lorentz oscillator model to describe in-plane dielectric response by
69 fitting the B-spline result.⁸

70 **Supplementary Equation 1.** Tauc-Lorentz oscillator.

$$71 \quad \varepsilon_2 = \begin{cases} \frac{1}{E} \cdot \frac{AE_0C(E-E_g)^2}{(E^2-E_0^2)^2+C^2E^2} & \text{for } E > E_g, \\ 0 & \text{for } E < E_g \end{cases},$$

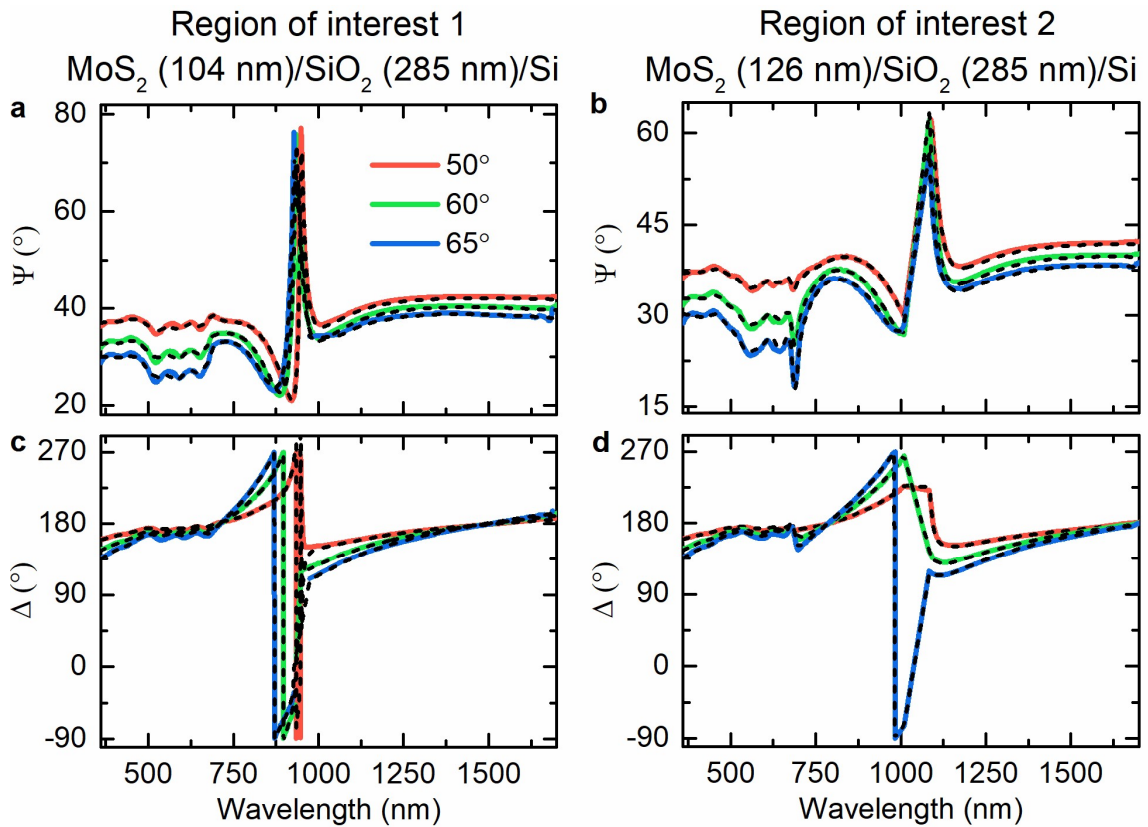
72 where E is the photon energy, A is the strength of the oscillator, C is the broadening term, E_g is the
73 optical band gap, and E_0 is the peak central energy with the real part of dielectric function derived
74 from the expression of ε_2 using Kramers-Kronig integration. Finally, we fitted the spectra in
75 Supplementary Figure 4 by varying the parameters of the Tauc-Lorentz oscillators and Cauchy
76 model with the results collected in Supplementary Table 1.

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79 **Supplementary Figure 3.** The scheme of spectroscopic ellipsometry measurements.



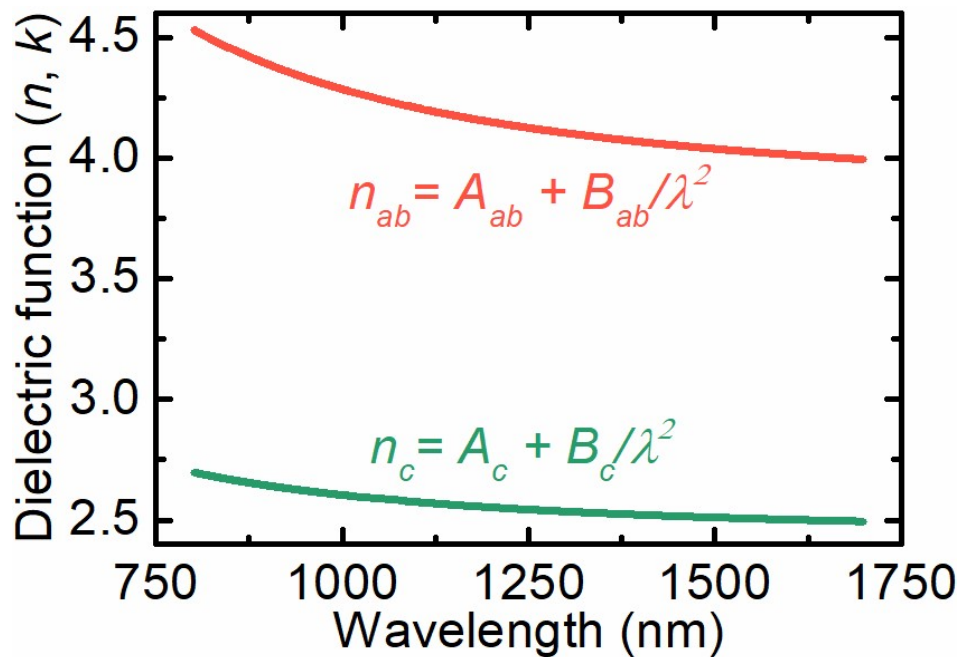
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81 **Supplementary Figure 4. a-d** Experimentally measured (solid lines) and calculated by Fresnel
 82 Formulas⁹ (dashed lines) for regions of interest (ROIs) 1 and 2 (shown in Figure 1b) ellipsometric
 83 parameters Ψ and Δ for the system MoS₂/SiO₂/Si at three incident angles (50°, 60°, and 65°). The
 84 asymmetrical interference-like peak at around 900 nm for ROI 1 and around 1100 nm for ROI 2
 85 is induced by interference enhancement in SiO₂ caused by splitting the incident beam into ordinary

86 and extraordinary rays. This prominent asymmetry for Ψ stems from giant anisotropy between the
87 c -axis and ab -plane.

88 In general, the fitting procedure described above could be summarized in 3 steps, which could be
89 successfully applied to similar TMDCs such as MoSe₂, WSe₂, WS₂, and MoTe₂ in 2H-
90 configuration. Note that we include in the physical model finite coherence of the light source
91 (bandwidth equals 5 nm for 360 – 1000 nm and 15 nm for 1000 – 1700 nm) to include the device
92 nonidealities:

93 **Step 1 (Transparent fitting region):** In the transparent range (800 – 1700 nm), both in-plane and
94 out-of-plane components were described by a Cauchy model $A + B/\lambda^2$. The fitting of Ψ and Δ by
95 Levenberg–Marquardt algorithm results in optical constants presented in Supplementary Figure 5:

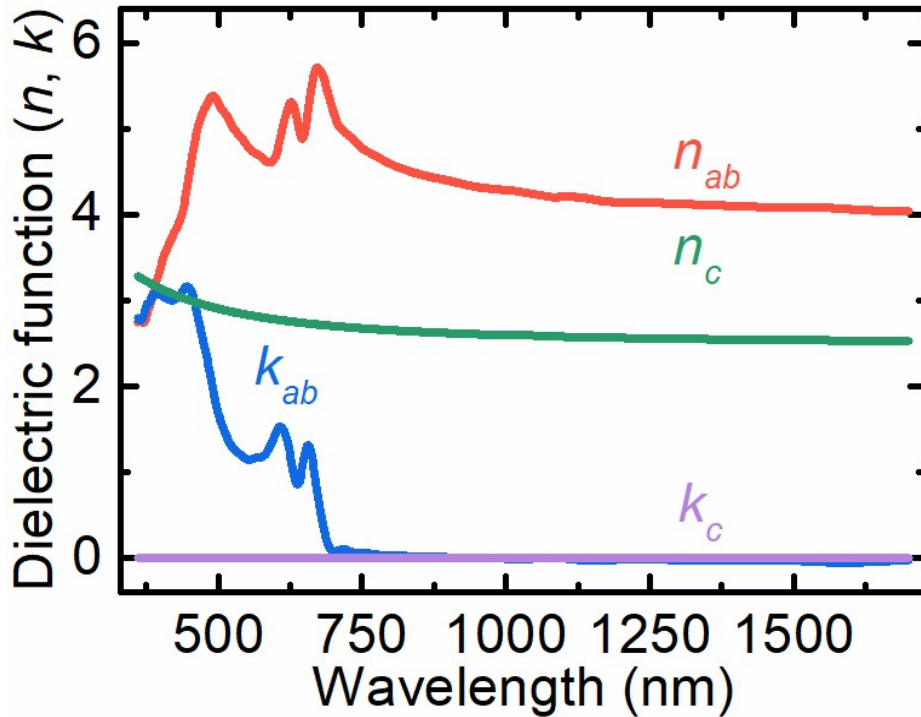


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97 **Supplementary Figure 5.** Optical constants of MoS₂ along the ab -plane and c -axis after step 1
98 with Cauchy parameters $A_{ab} = 3.84$, $B_{ab} = 0.44 \mu\text{m}^2$, $A_c = 2.44$, $B_c = 0.17 \mu\text{m}^2$.

99 **Step 2 (Wavelength expansion):** Next, the ab -plane dielectric function is approximated by
100 Kramers-Kronig B-splines⁷ placed equidistantly in the considered wavelength range with the step

101 of 0.05 eV, with subsequent expansion of the optical constants fitting to the whole wavelength
102 interval (360 – 1700 nm) by the method described in the work of Mohrmann and et al.⁷:



103

104 **Supplementary Figure 6.** Optical constants of MoS₂ along the *ab*-plane (B-splines) and *c*-axis
105 (Cauchy function) after step 2.

106 **Step 3 (Tauc-Lorentz description):** Although the previous step already gives decent results, it is
107 worth describing optical constants using the material properties since the B-spline approach tends
108 to provide unphysical optical constants.⁷ In the case of TMDCs, the best dielectric function for
109 describing their dielectric function is the Tauc-Lorentz oscillator model.⁸ It also allows for
110 obtaining more accurate values (Figure 2a) because of the reduction number of the fitting
111 parameters (from 57 to 21) with the best values collected in Supplementary Table 1.

112 **Supplementary Table 1.** Tauc-Lorentz parameters of the oscillators (excitons) describing the in-
113 plane dielectric response of MoS₂ with $\epsilon_\infty = 5.26 \pm 0.19$ and ultraviolet pole (unbroadened
114 oscillator) placed at 15 eV with amplitude equals to 228 ± 8 that affects the real part of the optical
115 constants by accounting for a strong absorption outside the measured spectrum. In contrast, the

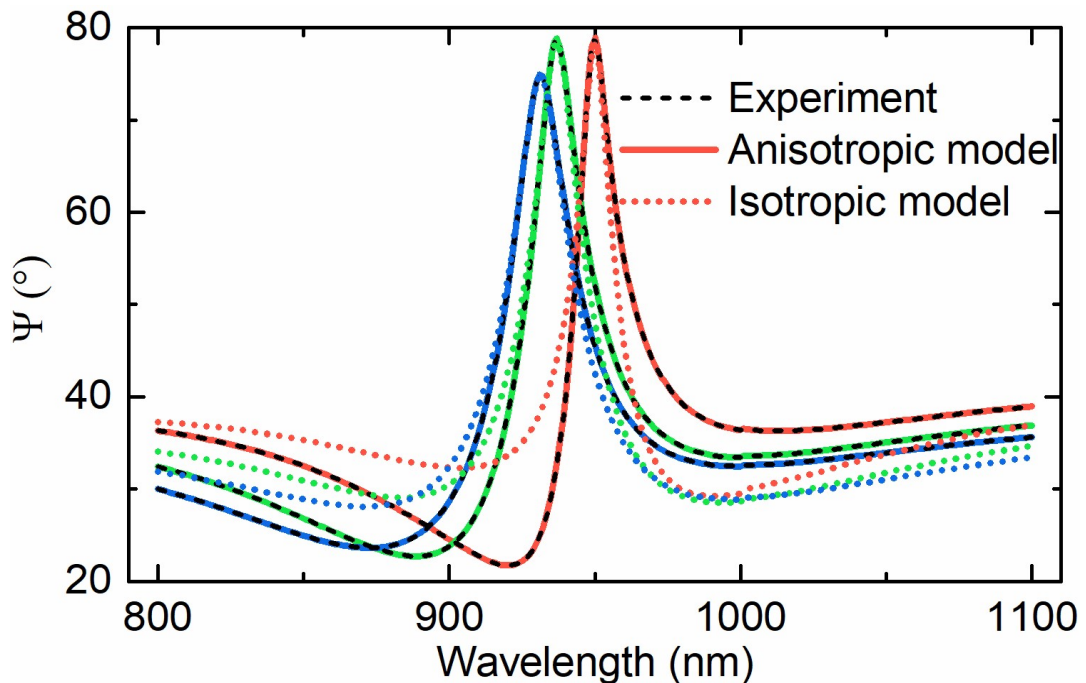
116 resulting Cauchy model for the out-of-plane component has $A = 2.463 \pm 0.009$ and $B = (119 \pm$
 117 $9) \cdot 10^3 \text{ nm}^2$.

Oscillator	A eV	E_0 eV	C meV	E_g eV
#1 (A-exciton)	308 ± 6	1.852 ± 0.002	67 ± 5	1.761 ± 0.009
#2 (B-exciton)	135 ± 5	2.006 ± 0.006	148 ± 14	1.82 ± 0.03
#3 (C-exciton)	19.3 ± 0.5	2.662 ± 0.005	380 ± 27	1.24 ± 0.12
#4 (C'-exciton)	69 ± 7	2.99 ± 0.03	1348 ± 39	1.31 ± 0.03

118

119 **Supplementary Note 3: Interference enhancement for anisotropic optical constants**
120 **determination**

121 Identification of anisotropic properties of high index semiconductors by traditional techniques
122 such as reflectance, transmission, and ellipsometry is a tedious task owing to the low sensitivity of
123 the signal to the out-of-plane permitting to a determination of only in-plane dielectric response.¹⁰
124 To overcome this obstacle, we used interference enhancement method. In the approach, the sample
125 of interest is placed on SiO₂/Si wafer. The SiO₂ layer accomplishes two functions. First of all, it
126 increases sensitivity to the p- and s-polarization reflection at the interface MoS₂/SiO₂ due to their
127 large difference in their refractive indices ($n_{ab} \sim 4$ and $n_c \sim 2.5$ for MoS₂ and $n \sim 1.4$ for SiO₂).
128 Secondly, oxide produces interference peaks (at 950 and 1090 nm in Figure S2a-b), which depends
129 on MoS₂ and SiO₂ thicknesses, allowing to implement Step 1 of the fitting procedure because of
130 the major difference between isotropic and anisotropic treatment in the peak vicinity as illustrated
131 in Supplementary Figure 7.

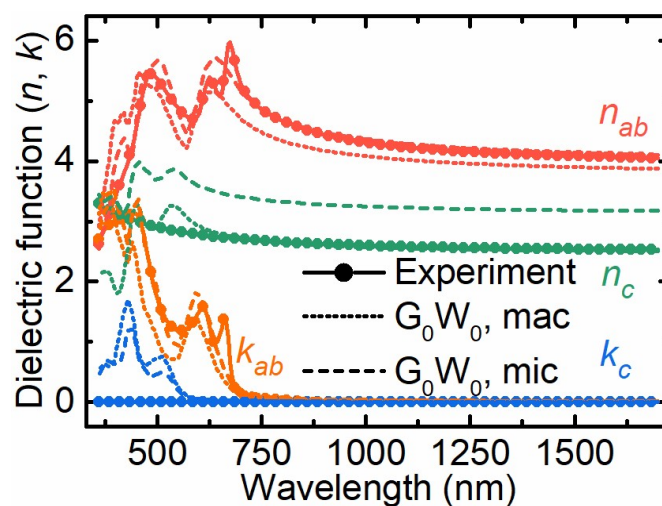


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133 **Supplementary Figure 7.** Interference peak caused by the SiO₂ layer in MoS₂ (104 nm)/SiO₂ (285
134 nm)/Si system. The giant anisotropy in MoS₂ transforms almost symmetrical peak into
135 asymmetrical.

136 **Supplementary Note 4: Dielectric permittivity of MoS₂ from first principles**

137 The comparison of the experimental data with first-principle calculations (see Methods) is
138 presented in Supplementary Figure 8. Our experimental results qualitatively and in the infrared
139 region, even quantitatively agree with the first-principles calculations, which further validate our
140 findings. The small mismatch is likely attributed to the approximations used in DFT analysis since
141 near-field measurements reproduced our dielectric function at 1470 – 1570 and 632.8 nm in the
142 main text. Surprisingly, the in-plane component of the dielectric permittivity tensor is better
143 described by the microscopic dielectric function, whereas the out-of-plane component is better
144 described by the macroscopic dielectric function (for the rigorous definitions of micro- and
145 macroscopic dielectric response see the book of Bechstedt¹¹). Clearly, our findings indicate that
146 for layered materials, the physical origins for the spectral behavior of the in-plane and out-of-plane
147 components of the dielectric permittivity tensor are different and cannot be treated in the same
148 way. To date, the authors believe that this phenomenon stems from the similarity of *ab*-plane to
149 monolayer structure, where the local effects (microscopic) play a significant role in optical
150 response. Still, further studies are needed to clarify the observed effect, which is fundamental for
151 *ab initio* study of the layered materials.



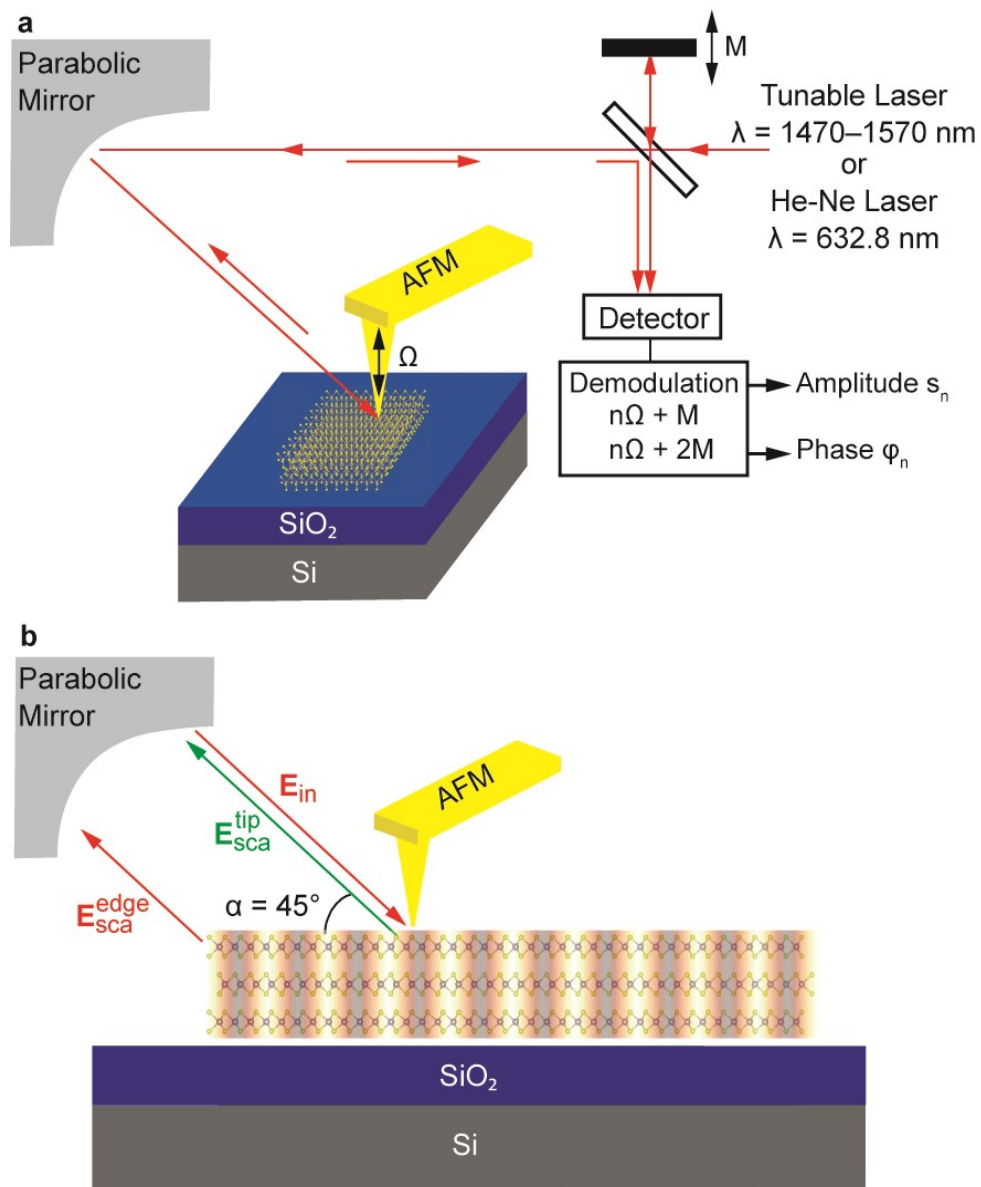
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153 **Supplementary Figure 8.** Comparison between experimental and DFT predicted macroscopic
154 (mac) and microscopic (mic) optical constants along the crystallographic *ab*-plane and *c*-axis.

155 **Supplementary Note 5: Near-field imaging of a planar waveguide mode within MoS₂ flake**
156 **and extreme skin depth in silicon**

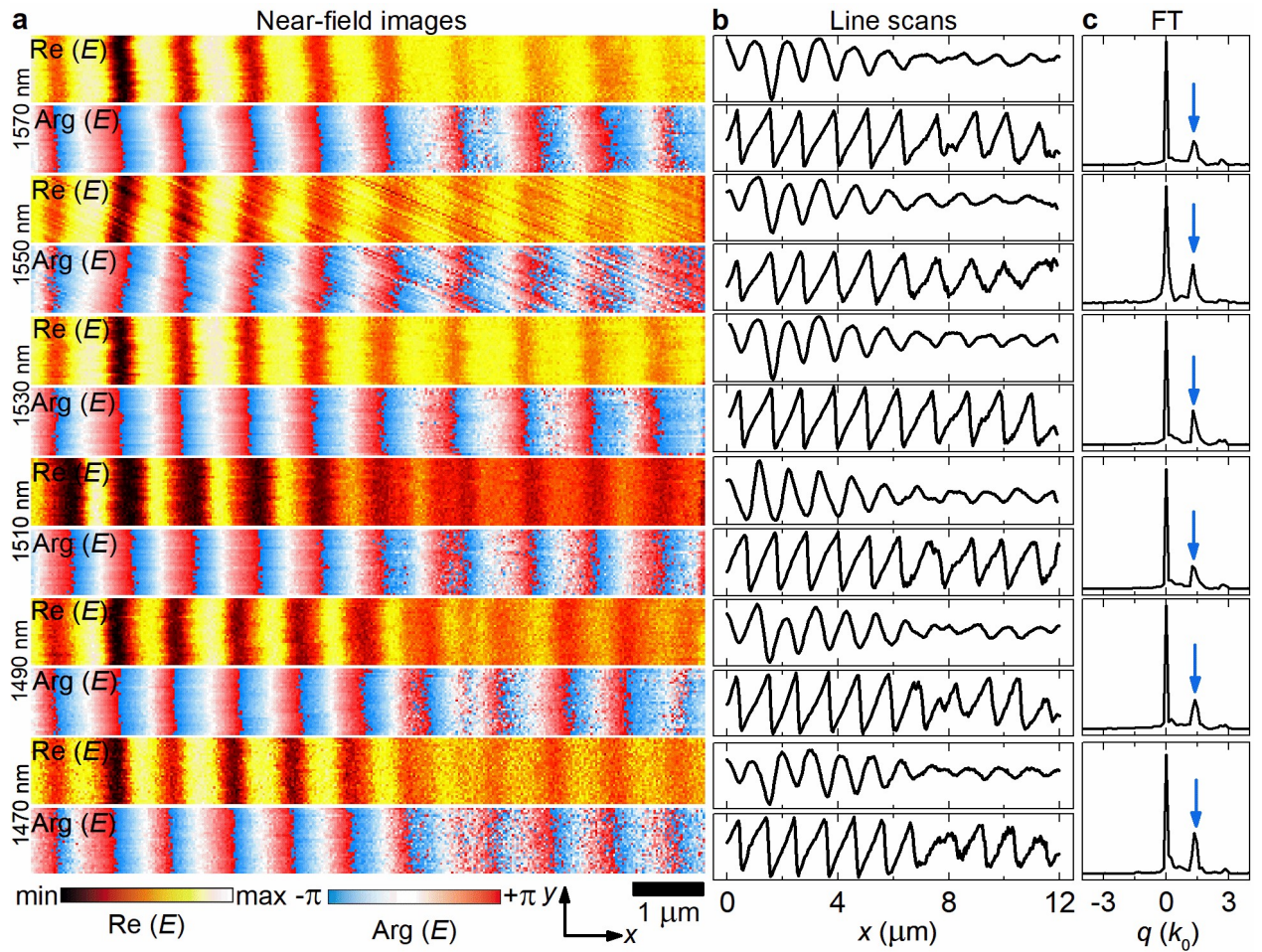
157 To analyze the planar waveguide modes in MoS₂ flake and silicon waveguide on MoS₂ with
158 extreme skin-depth at multiple wavelengths, we performed scattering-type near-field optical
159 microscopy (s-SNOM), which scheme is presented in Supplementary Figure 9. The resulting
160 signals are an oscillation of light intensity induced by the tip and edge-scattered photons, as clearly
161 seen in Supplementary Figures 10-12. To analyze the effective mode index, we carried out the
162 complex Fourier transformation (FT). Unlike the widely used real FT, it takes into account the real
163 and imaginary signals at the same time and thus more precise, as could be understood from
164 Supplementary Figure 13. Furthermore, it provides additional information about the predominant
165 scattering mechanism. Mainly, there are no peaks for the negative values of q in Supplementary
166 Figures 10-12c, indicating that no modes propagate in the backward direction (from the edge to
167 the tip).

168 Besides, it is worth to discuss the absence of TM₃, TM₂, and TM₀ modes at $\lambda = 632.8$ nm in the
169 measured signal in Supplementary Figure 13a. The first two TM₃ and TM₂ could not propagate
170 because their figure of merit or, in other words, the possible number of observed fringes, is less
171 than unity; while the coupling efficiency f with an s-SNOM tip for TM₀ ($f = 0.016$) is much lower
172 than for TM₁ ($f = 0.043$) as demonstrated in Supplementary Figure 14, thus explaining the
173 predominant behavior of TM₁ in the measured signal in Supplementary Figure 11.



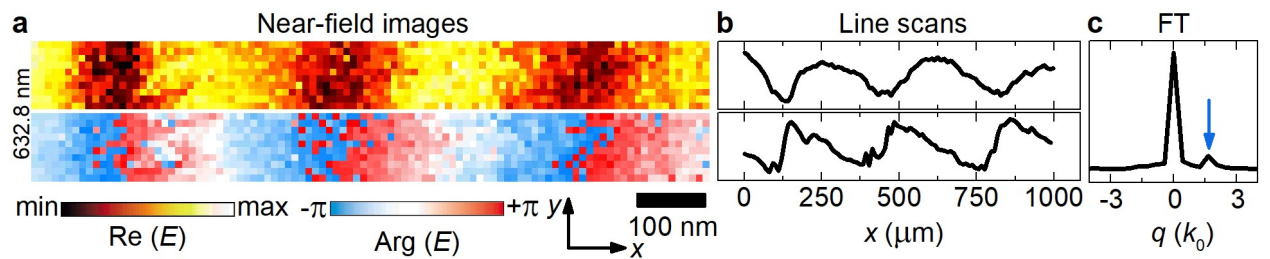
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175 **Supplementary Figure 9. a** Schematic of the s-SNOM experimental configuration used to image
 176 MoS_2 flake. A metalized AFM tip is illuminated by p-polarized light of wavelength λ . It launches
 177 a planar waveguide mode, which interferes with the illuminating plane wave and gets scattered at
 178 the sample edge to the far-field, where a distant detector collects it. **b** Illustration of waveguide
 179 mode tip excitation and following scattering at the flake's edge.



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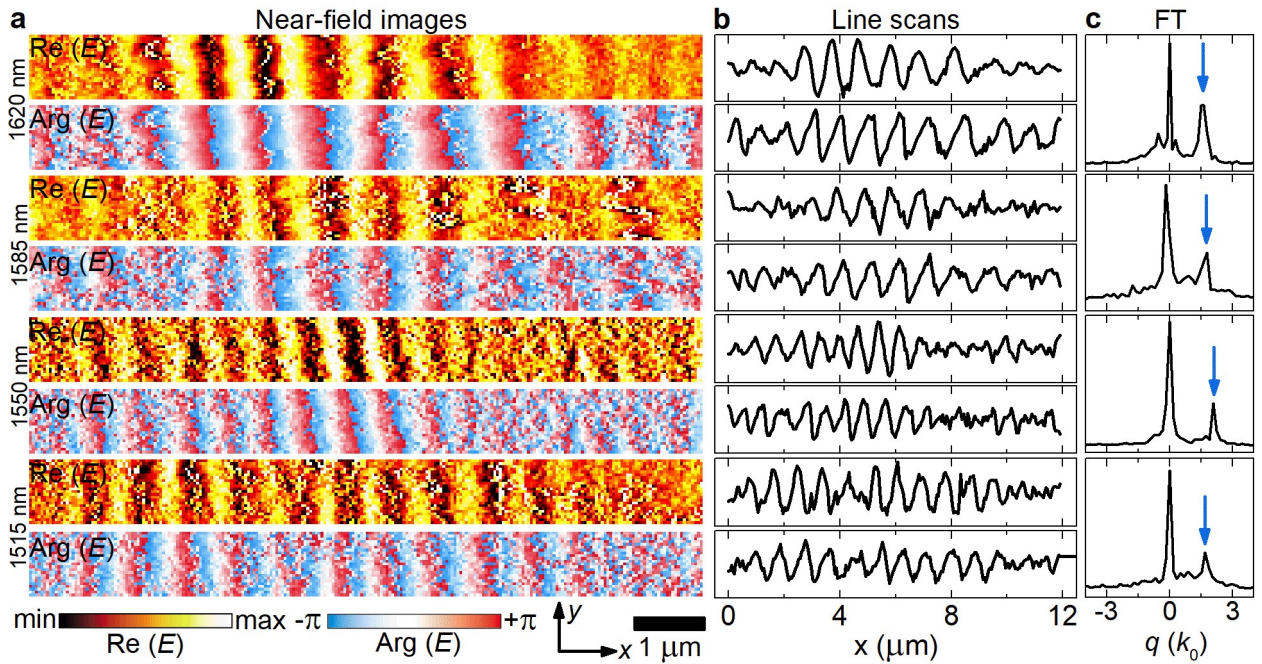
181 **Supplementary Figure 10. a** Near-field images, real part $\text{Re}(E)$ and phase $\text{Arg}(E)$, of electric field
 182 E taken at 1570 – 1470 (from top to bottom) in an area of the image in Figure 3b, indicated by a
 183 blue rectangular. **b** x -line scans taken from **(a)** and averaged over $1.2\ \mu\text{m}$ along the y -axis. **c** Fourier
 184 transform (FT) amplitude of the complex near-field signal in **(b)**, the blue arrow marks the peak
 185 associated with waveguide mode.



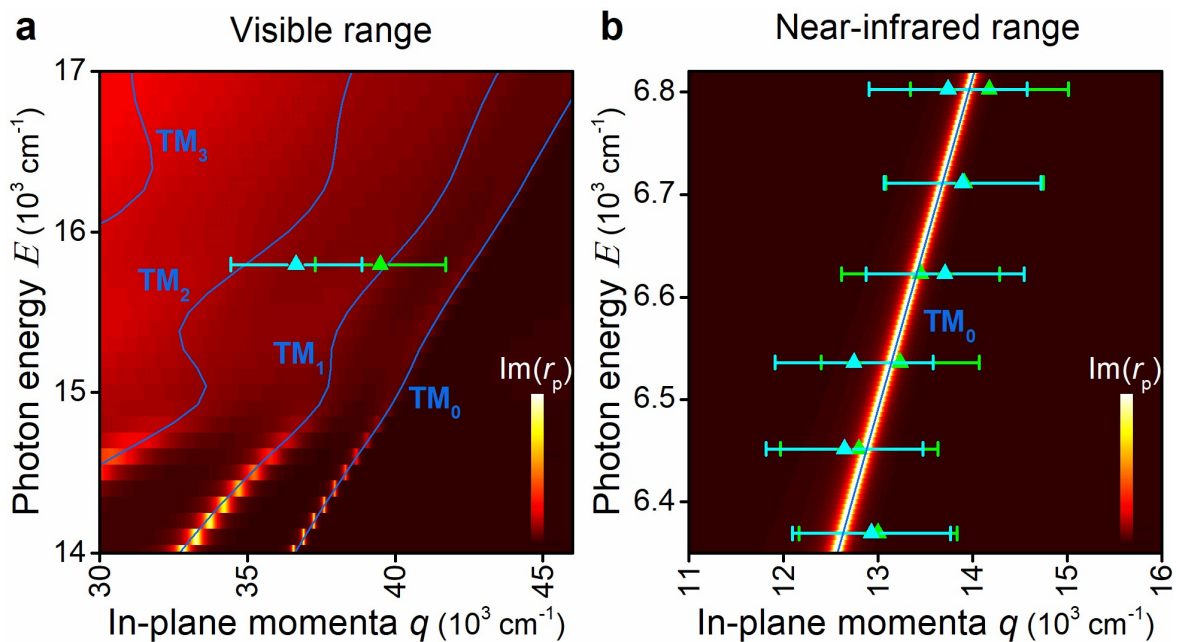
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187 **Supplementary Figure 11. a** Near-field images, real part $\text{Re}(E)$ and phase $\text{Arg}(E)$, of electric field
 188 E taken at 632.8 nm in an area of the image in Figure 3b, indicated by a blue rectangular. **b** x -line
 189 scans taken from **(a)** and averaged over $1.2\ \mu\text{m}$ along the y -axis. **c** Fourier transform (FT)

190 amplitude of the complex near-field signal in **(b)**, the blue arrow marks the peak associated with
 191 waveguide mode.

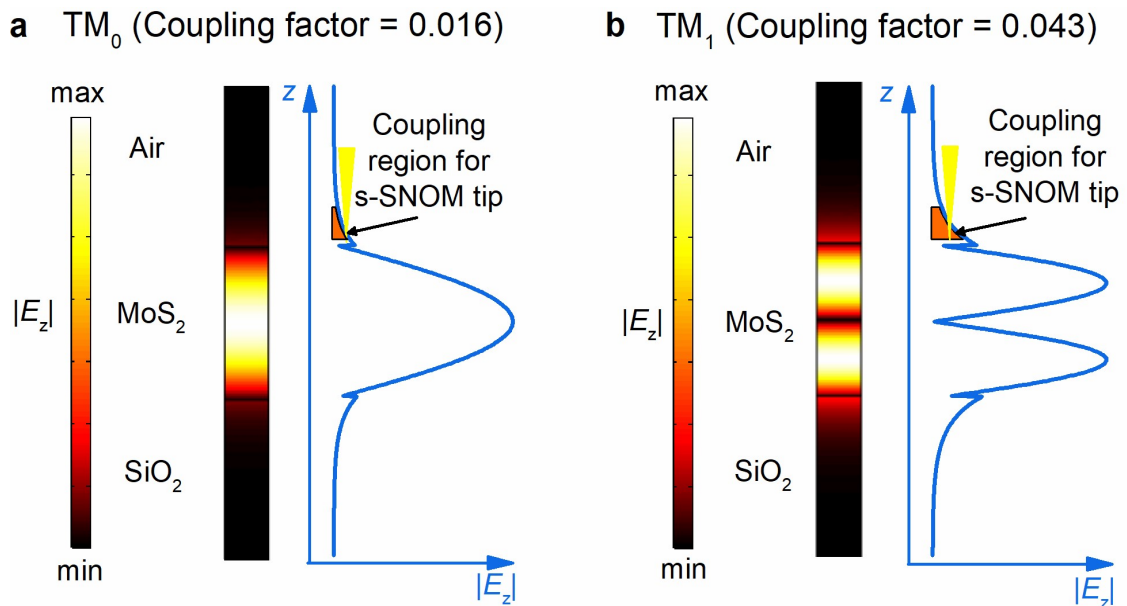


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 193 **Supplementary Figure 12.** **a** Near-field images, real part $\text{Re}(E)$ and phase $\text{Arg}(E)$, of electric field
 194 E taken at 632.8 nm in an area of the image in Figure 5g-h, indicated by a green rectangular. **b** x -
 195 line scans taken from **(a)** and averaged over 1.2 μm along the y -axis. **c** Fourier transform (FT)
 196 amplitude of the complex near-field signal in **(b)**, the blue arrow marks the peak associated with
 197 waveguide mode.



198

199 **Supplementary Figure 13.** Comparison of the different analyses of near-field signal with green
 200 and cyan triangles corresponding to complex and real FT, respectively, for **a** visible and **b** near-
 201 infrared wavelength ranges. Meanwhile, in the near-infrared interval, different approaches yield
 202 the same result; for visible range, the difference is striking with complex FT, giving much better
 203 agreement with the theory prediction.



204

205 **Supplementary Figure 14.** Coupling efficiency comparison of waveguide near-field with s-
 206 SNOM tip at $\lambda = 632.8$ nm for **a** TM_0 and **b** TM_1 modes. Clearly, the coupling factor for TM_1
 207 (0.043) is much higher than for TM_0 (0.016), thus explaining the predominant behavior in the
 208 measured signal for TM_1 in Supplementary Figure 13.

209

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